1795

b Receipt date: 03/31/2008						10594282 - GAU:			
						SHE	ET	1 OF 1	
Form PTO 1449		U.S. DEPARTMENT OF O	COMMERCE	ATTY DOCKET NO.		SERIAL NO.			
(Modified) PATENT AND TRADEMARK OFFICE			295727US0PCT		10/594,282				
				APPLICANT					
LIST OF	REFE	RENCES CITED BY APPLI	CANT	Hirotoshi ISHII, et al.					
				FILING DATE		GROUP			
				September 26, 2006		1752			
				U.S. PATENT DOCUMENTS					
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS		FILING DATE APPROPRIATE	
	AA								
	AB								
	AC								
	AD								
	AF								
	AF								
	AC								
	AH								
	Al								
	AJ								
	AK								
	AF								
	AM								
	AN								
			FO	REIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY			TRANS	SLATION NO	
	AD								
	AF								
	AD								
	ΑK								
	AS								
	AT								
	AU								
	ΑV								
		OTHER REFE	RENCES (I	ncluding Author, Title, Date, Pertine	nt Pages, et	c.)			
/SL/	AW	Osamu HABA, et al., "A New Photoresist Based on Calix [4] resorcinarene Dendrimer", CHEMISTRY OF MATERIALS, VOL. 11, No. 2, XP-002470141, 1999, pages 427-432							
	AX								

AY ΑZ Additional References sheet(s) attached Examiner /Sin Lee/ Date Considered 04/27/2008

*Examiner. Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.